

# Lecture 2

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## OUTLINE

- Basic Semiconductor Physics (cont'd)
  - Carrier drift and diffusion
- PN Junction Diodes
  - Electrostatics
  - Capacitance

Reading: Chapter 2.1-2.2

# Dopant Compensation

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- An N-type semiconductor can be converted into P-type material by counter-doping it with acceptors such that  $N_A > N_D$ .
- A ***compensated semiconductor material*** has both acceptors and donors.

N-type material

$$(N_D > N_A)$$

$$n \approx N_D - N_A$$

$$p \approx \frac{n_i^2}{N_D - N_A}$$

P-type material

$$(N_A > N_D)$$

$$p \approx N_A - N_D$$

$$n \approx \frac{n_i^2}{N_A - N_D}$$

# Types of Charge in a Semiconductor

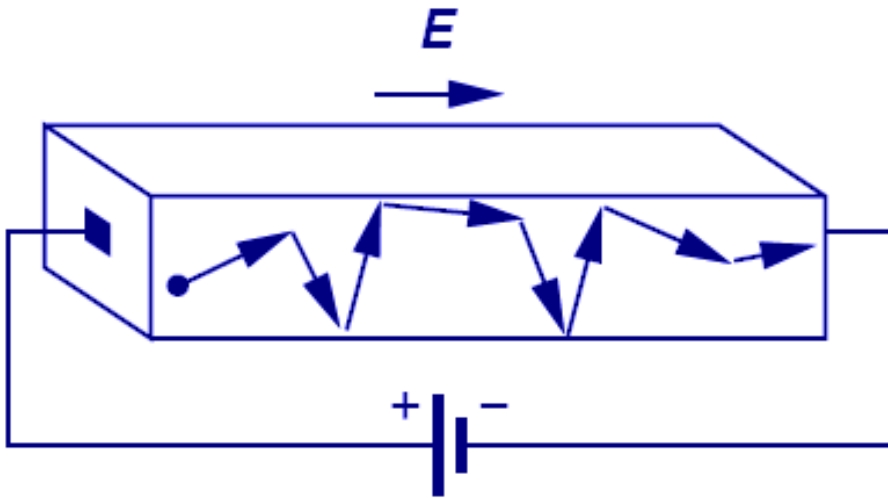
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- Negative charges:
  - Conduction electrons (density =  $n$ )
  - Ionized acceptor atoms (density =  $N_A$ )
- Positive charges:
  - Holes (density =  $p$ )
  - Ionized donor atoms (density =  $N_D$ )
- The net charge density (C/cm<sup>3</sup>) in a semiconductor is

$$\rho = q(p - n + N_D - N_A)$$

# Carrier Drift

- The process in which charged particles move because of an electric field is called **drift**.
- Charged particles within a semiconductor move with an average velocity proportional to the electric field.
  - The proportionality constant is the carrier **mobility**.



$$\text{Hole velocity } \vec{v}_h = \mu_p \vec{E}$$

$$\text{Electron velocity } \vec{v}_e = -\mu_n \vec{E}$$

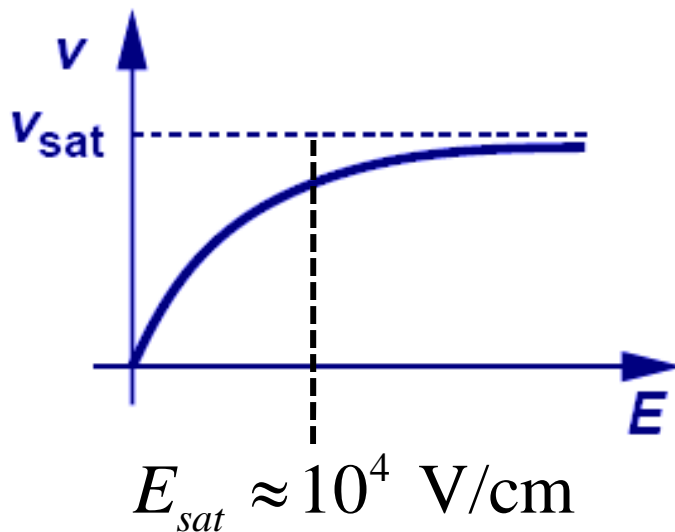
**Notation:**

$\mu_p \equiv$  hole mobility ( $\text{cm}^2/\text{V}\cdot\text{s}$ )

$\mu_n \equiv$  electron mobility ( $\text{cm}^2/\text{V}\cdot\text{s}$ )

# Velocity Saturation

- In reality, carrier velocities saturate at an upper limit, called the *saturation velocity* ( $v_{sat}$ ).



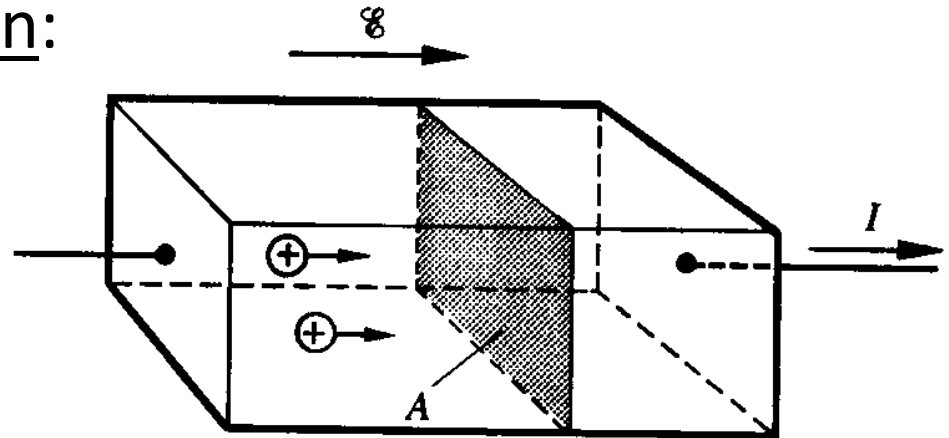
$$\mu = \frac{\mu_0}{1 + bE}$$

$$v_{sat} = \frac{\mu_0}{b}$$

$$v = \frac{\mu_0}{1 + \frac{\mu_0 E}{v_{sat}}} E$$

# Drift Current

- Drift current is proportional to the carrier velocity and carrier concentration:



$v_h t A$  = volume from which all holes cross plane in time  $t$

$p v_h t A$  = # of holes crossing plane in time  $t$

$q p v_h t A$  = charge crossing plane in time  $t$

$q p v_h A$  = charge crossing plane per unit time = hole current

➔ **Hole current per unit area (i.e. current density)  $J_{p,\text{drift}} = q p v_h$**

# Conductivity and Resistivity

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- In a semiconductor, both electrons and holes conduct current:

$$J_{p,drift} = q p \mu_p E \quad J_{n,drift} = -q n (-\mu_n E)$$

$$J_{tot,drift} = J_{p,drift} + J_{n,drift} = q p \mu_p E + q n \mu_n E$$

$$J_{tot,drift} = q(p \mu_p + n \mu_n) E \equiv \sigma E$$

- Conductivity

$$\sigma \equiv q p \mu_p + q n \mu_n \quad [\text{unit: mho/cm} = \text{S/cm}]$$

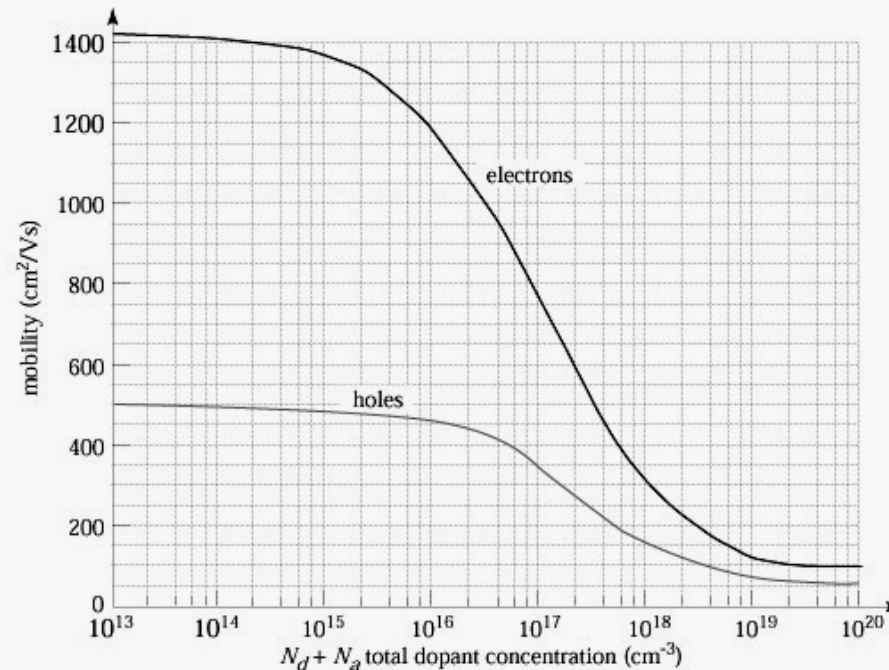
- Resistivity

$$\rho \equiv \frac{1}{\sigma} \quad [\text{Unit: } \Omega\text{-cm}]$$

- Typical resistivity range for Si:  $10^{-3} \sim 10^3 \Omega\text{-cm}$

# Resistivity Example

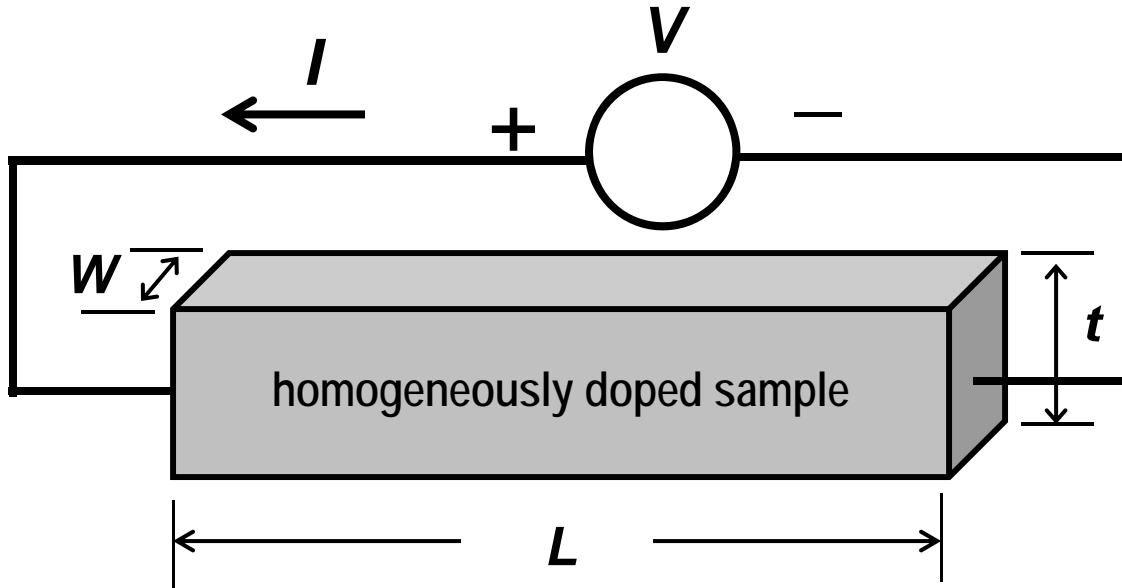
- Estimate the resistivity of a Si sample doped with phosphorus to a concentration of  $10^{15} \text{ cm}^{-3}$  and boron to a concentration of  $10^{17} \text{ cm}^{-3}$ . The electron mobility and hole mobility are  $800 \text{ cm}^2/\text{Vs}$  and  $300 \text{ cm}^2/\text{Vs}$ , respectively.





# Electrical Resistance

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**Resistance**

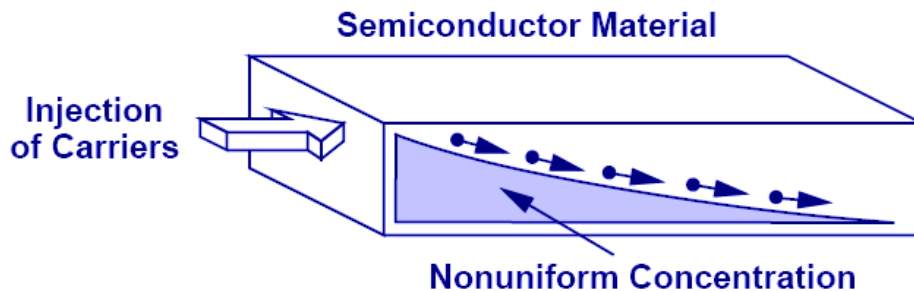
$$R \equiv \frac{V}{I} = \rho \frac{L}{Wt}$$

**(Unit: ohms)**

where  $\rho$  is the resistivity

# Carrier Diffusion

- Due to thermally induced random motion, mobile particles tend to move from a region of high concentration to a region of low concentration.
  - Analogy: ink droplet in water
- Current flow due to mobile charge diffusion is proportional to the carrier concentration gradient.
  - The proportionality constant is the ***diffusion constant***.



$$J_p = -qD_p \frac{dp}{dx}$$

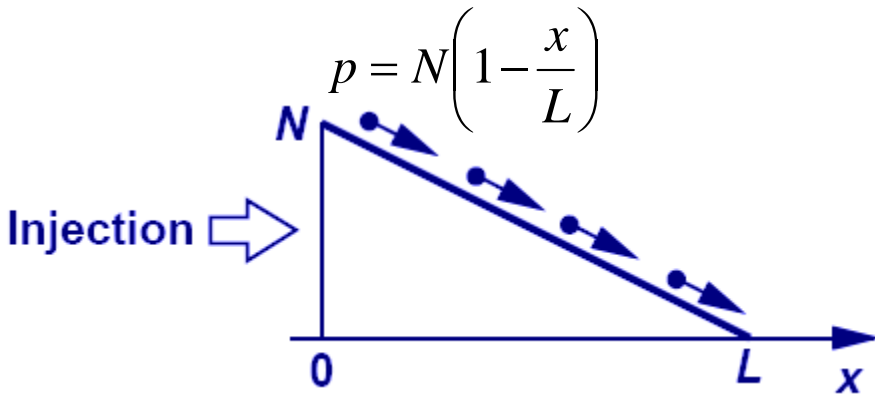
**Notation:**

$D_p \equiv$  hole diffusion constant (cm<sup>2</sup>/s)

$D_n \equiv$  electron diffusion constant (cm<sup>2</sup>/s)

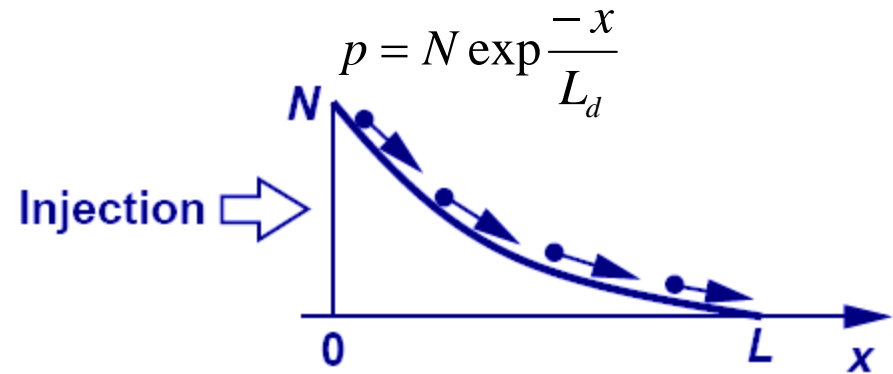
# Diffusion Examples

- Linear concentration profile  
→ constant diffusion current



$$J_{p,diff} = -qD_p \frac{dp}{dx}$$
$$= qD_p \frac{N}{L}$$

- Non-linear concentration profile  
→ varying diffusion current



$$J_{p,diff} = -qD_p \frac{dp}{dx}$$
$$= \frac{qD_p N}{L_d} \exp\left(-\frac{x}{L_d}\right)$$

# Diffusion Current

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- Diffusion current within a semiconductor consists of hole and electron components:

$$J_{p,diff} = -qD_p \frac{dp}{dx} \quad J_{n,diff} = qD_n \frac{dn}{dx}$$

$$J_{tot,diff} = q\left(D_n \frac{dn}{dx} - D_p \frac{dp}{dx}\right)$$

- The total current flowing in a semiconductor is the sum of drift current and diffusion current:

$$J_{tot} = J_{p,drift} + J_{n,drift} + J_{p,diff} + J_{n,diff}$$

# The Einstein Relation

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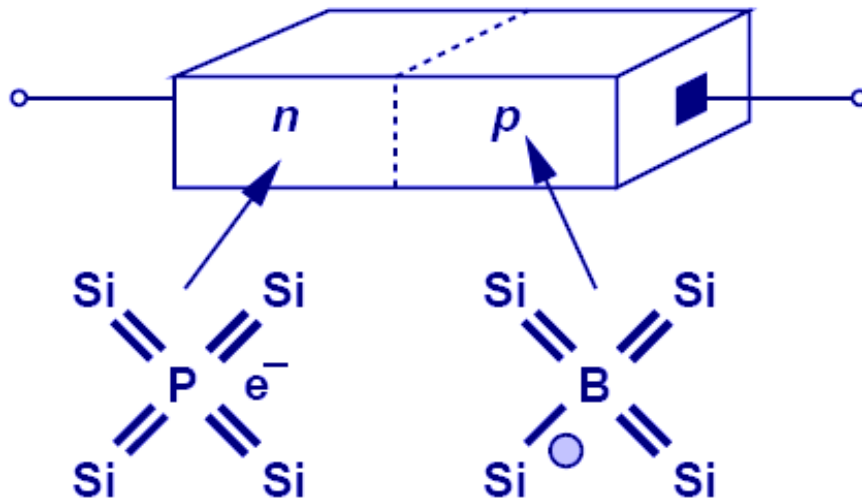
- The characteristic constants for drift and diffusion are related:

$$\boxed{\frac{D}{\mu} = \frac{kT}{q}}$$

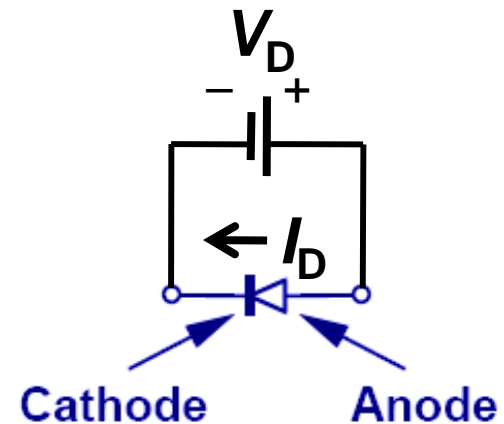
- Note that  $\frac{kT}{q} \cong 26\text{mV}$  at room temperature (300K)
  - This is often referred to as the “thermal voltage”.

# The PN Junction Diode

- When a P-type semiconductor region and an N-type semiconductor region are in contact, a PN junction diode is formed.



(a)



(b)

# Diode Operating Regions

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- In order to understand the operation of a diode, it is necessary to study its behavior in three operation regions: equilibrium, reverse bias, and forward bias.

$$V_D = 0$$

PN Junction  
in Equilibrium

- Depletion Region
- Built-in Potential



$$V_D < 0$$

PN Junction  
Under Reverse Bias

- Junction Capacitance



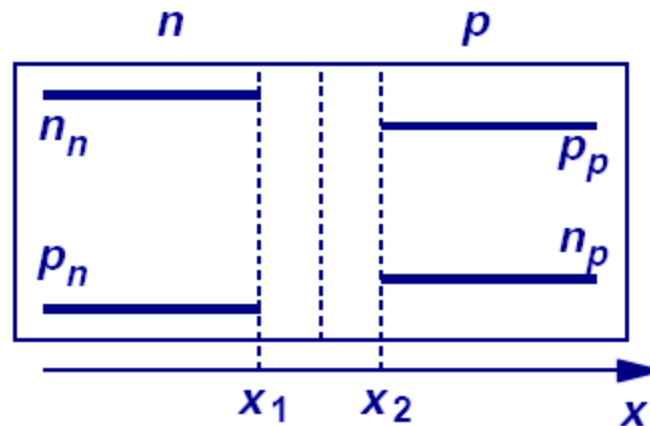
$$V_D > 0$$

PN Junction  
Under Forward Bias

- I/V Characteristics

# Carrier Diffusion across the Junction

- Because of the difference in hole and electron concentrations on each side of the junction, carriers diffuse across the junction:



## Notation:

$n_n \equiv$  electron concentration on N-type side ( $\text{cm}^{-3}$ )

$p_n \equiv$  hole concentration on N-type side ( $\text{cm}^{-3}$ )

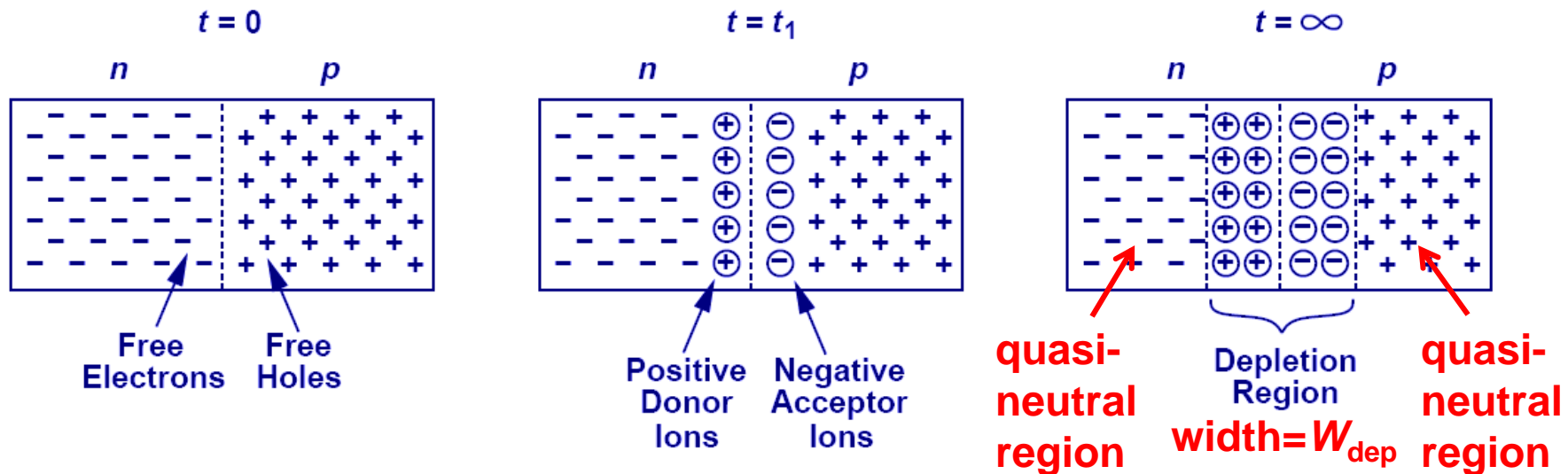
$p_p \equiv$  hole concentration on P-type side ( $\text{cm}^{-3}$ )

$n_p \equiv$  electron concentration on P-type side ( $\text{cm}^{-3}$ )

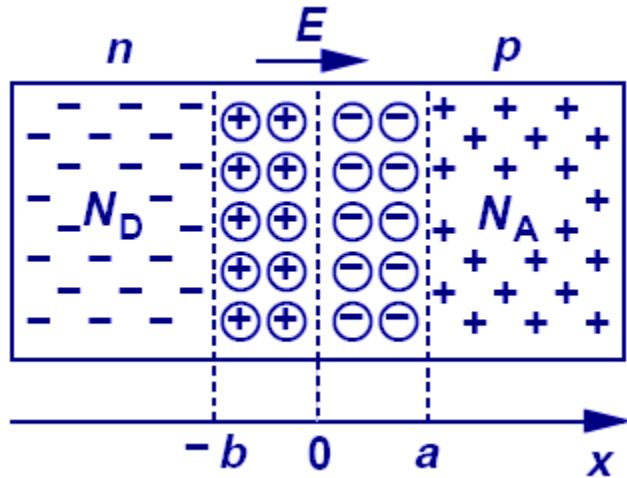


# Depletion Region

- As conduction electrons and holes diffuse across the junction, they leave behind ionized dopants. Thus, a region that is depleted of mobile carriers is formed.
  - The charge density in the depletion region is not zero.
  - The carriers which diffuse across the junction recombine with majority carriers, *i.e.* they are annihilated.



# The Depletion Approximation



In the depletion region on the **N side**:

$$\frac{dE}{dx} = \frac{\rho}{\epsilon_{si}} = \frac{qN_D}{\epsilon_{si}} \quad \text{Gauss's Law}$$

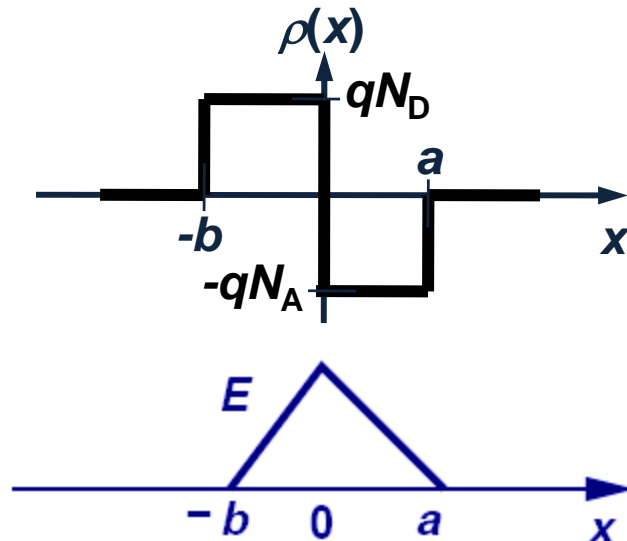
$$E = \frac{qN_D}{\epsilon_{si}}(x + b) \quad \epsilon_{si} = 10^{12} \text{ F/cm}$$

In the depletion region on the **P side**:

$$\frac{dE}{dx} = \frac{\rho}{\epsilon_{si}} = \frac{-qN_A}{\epsilon_{si}}$$

$$E = \frac{qN_A}{\epsilon_{si}}(a - x)$$

$$aN_A = bN_D$$



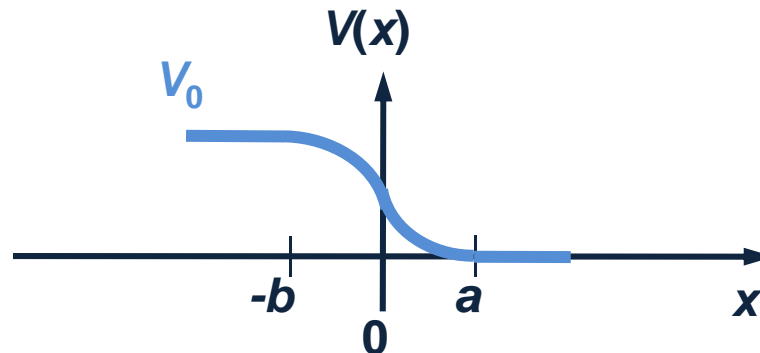
# Potential Distribution

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- In the depletion region, the electric potential is quadratic since the electric field is linear
- The potential difference between the N and the P side is called built-in potential,  $V_0$

$$E = -\frac{dV}{dx}$$

$$V = -\int E \cdot dx$$



# PN Junction in Equilibrium

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- In equilibrium, the drift and diffusion components of current are balanced; therefore the net current flowing across the junction is zero.

$$J_{p,drift} = -J_{p,diff}$$

$$J_{n,drift} = -J_{n,diff}$$

$$J_{tot} = J_{p,drift} + J_{n,drift} + J_{p,diff} + J_{n,diff} = 0$$

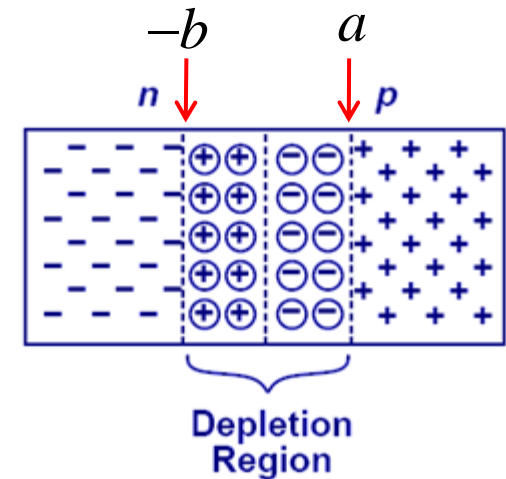
# Built-in Potential, $V_0$

- Because of the electric field in the depletion region, there exists a potential drop across the junction:

$$qp\mu_p E = qD_p \frac{dp}{dx} \quad \Rightarrow \quad p\mu_p \left( -\frac{dV}{dx} \right) = D_p \frac{dp}{dx}$$

$$\Rightarrow \quad -\mu_p \int_{-b}^a dV = D_p \int_{p_n}^{p_p} \frac{dp}{p}$$

$$\Rightarrow \quad V(-b) - V(a) = \frac{D_p}{\mu_p} \ln \frac{p_p}{p_n} = \frac{kT}{q} \ln \frac{N_A}{(n_i^2 / N_D)}$$



$$V_0 = \frac{kT}{q} \ln \frac{N_A N_D}{n_i^2}$$

**(Unit: Volts)**

# Built-In Potential Example

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- Estimate the built-in potential for PN junction below.

N	P
$N_D = 10^{18} \text{ cm}^{-3}$	$N_A = 10^{15} \text{ cm}^{-3}$

$$V_0 = \frac{kT}{q} \ln \left( \frac{N_D N_A}{n_i^2} \right) = (26\text{mV}) \ln \left( \frac{10^{18} 10^{15}}{10^{20}} \right) = (26\text{mV}) \ln (10^{13})$$

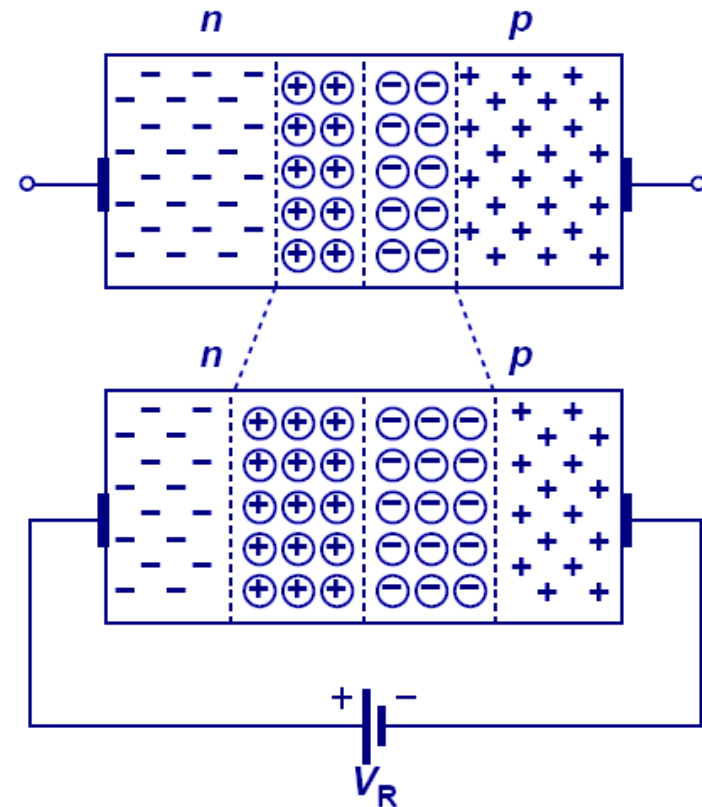
$$\text{Note: } \frac{kT}{q} \ln(10) \cong 26\text{mV} \times 2.3 \cong 60\text{mV}$$

$$V_0 = 60\text{mV} \times 13 = 780\text{mV}$$

# PN Junction under Reverse Bias

- A reverse bias increases the potential drop across the junction. As a result, the magnitude of the electric field increases and the width of the depletion region widens.

$$W_{dep} = \sqrt{\frac{2\epsilon_{si}}{q} \left( \frac{1}{N_A} + \frac{1}{N_D} \right) (V_0 + V_R)}$$



# Diode Current under Reverse Bias

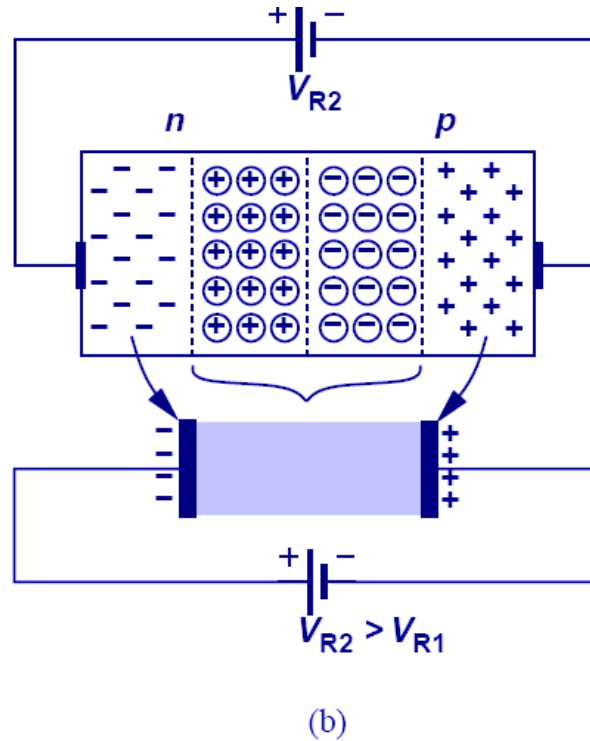
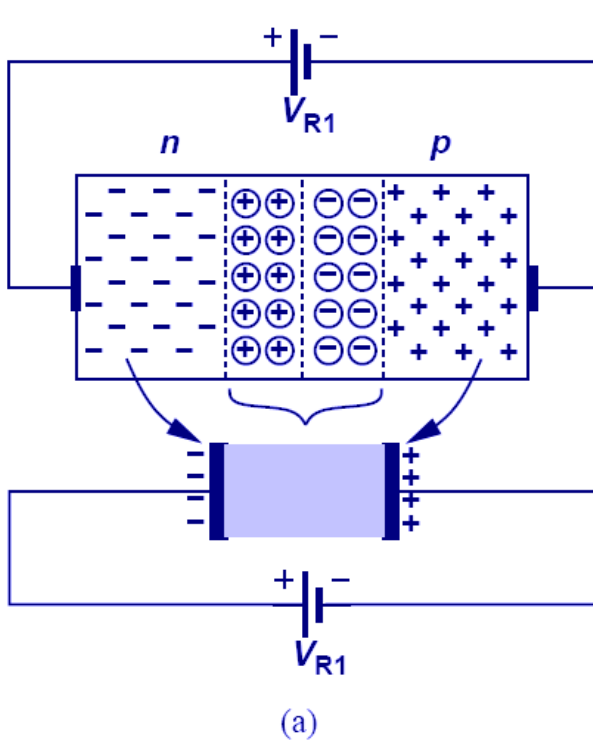
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- In equilibrium, the built-in potential effectively prevents carriers from diffusing across the junction.
- Under reverse bias, the potential drop across the junction increases; therefore, negligible diffusion current flows. **A very small drift current flows**, limited by the rate at which minority carriers diffuse from the quasi-neutral regions into the depletion region.



# PN Junction Capacitance

- A reverse-biased PN junction can be viewed as a capacitor. The depletion width ( $W_{dep}$ ) and hence the junction capacitance ( $C_j$ ) varies with  $V_R$ .

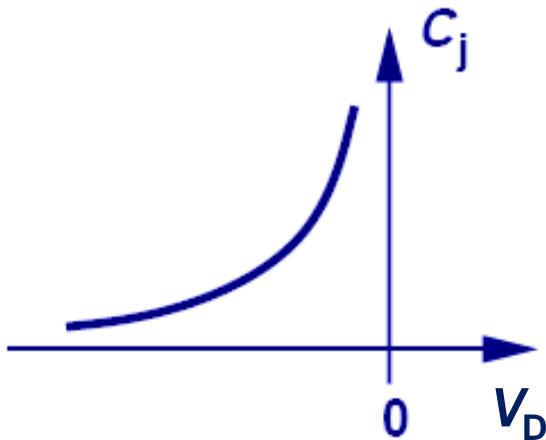


$$C_j = \frac{\epsilon_{si}}{W_{dep}}$$

[F/cm<sup>2</sup>]

# Voltage-Dependent Capacitance

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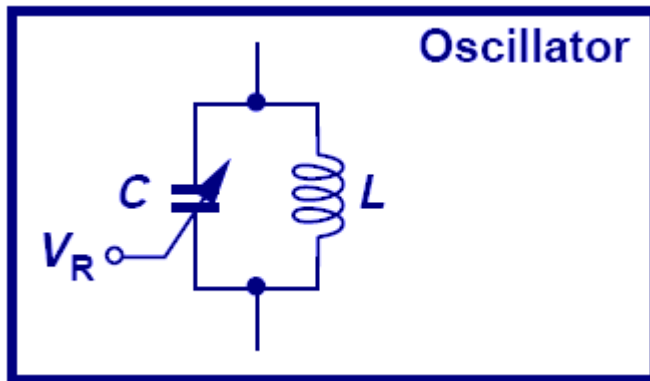
$$C_j = \frac{C_{j0}}{\sqrt{1 + \frac{V_R}{V_0}}}$$

$$C_{j0} = \sqrt{\frac{\epsilon_{si} q}{2} \frac{N_A N_D}{N_A + N_D} \frac{1}{V_0}}$$

$\epsilon_{si} \cong 10^{-12}$  F/cm is the permittivity of silicon

# Reverse-Biased Diode Application

- A very important application of a reverse-biased PN junction is in a voltage controlled oscillator (VCO), which uses an LC tank. By changing  $V_R$ , we can change  $C$ , which changes the oscillation frequency.



$$f_{res} = \frac{1}{2\pi} \frac{1}{\sqrt{LC}}$$

# Summary

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- Current flowing in a semiconductor is comprised of drift and diffusion components:  $J_{tot} = qp\mu_p E + qn\mu_n E + qD_n \frac{dn}{dx} - qD_p \frac{dp}{dx}$
- A region depleted of mobile charge exists at the junction between P-type and N-type materials.
  - A built-in potential drop ( $V_0$ ) across this region is established by the charge density profile; it opposes diffusion of carriers across the junction. A reverse bias voltage serves to enhance the potential drop across the depletion region, resulting in very little (drift) current flowing across the junction.
  - The width of the depletion region ( $W_{dep}$ ) is a function of the bias voltage ( $V_D$ ).

$$W_{dep} = \sqrt{\frac{2\epsilon_{si}}{q} \left( \frac{1}{N_A} + \frac{1}{N_D} \right) (V_0 - V_D)}$$

$$V_0 = \frac{kT}{q} \ln \frac{N_A N_D}{n_i^2}$$